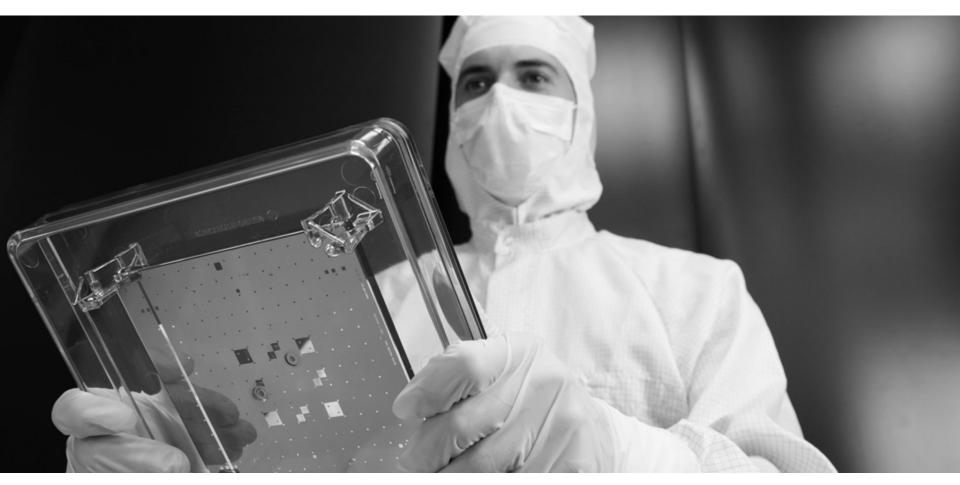
AIMS[™] EUV

Status and recent achievements of the AIMS[™] EUV System for Actinic Review of EUV masks





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Oct 5th, 2015



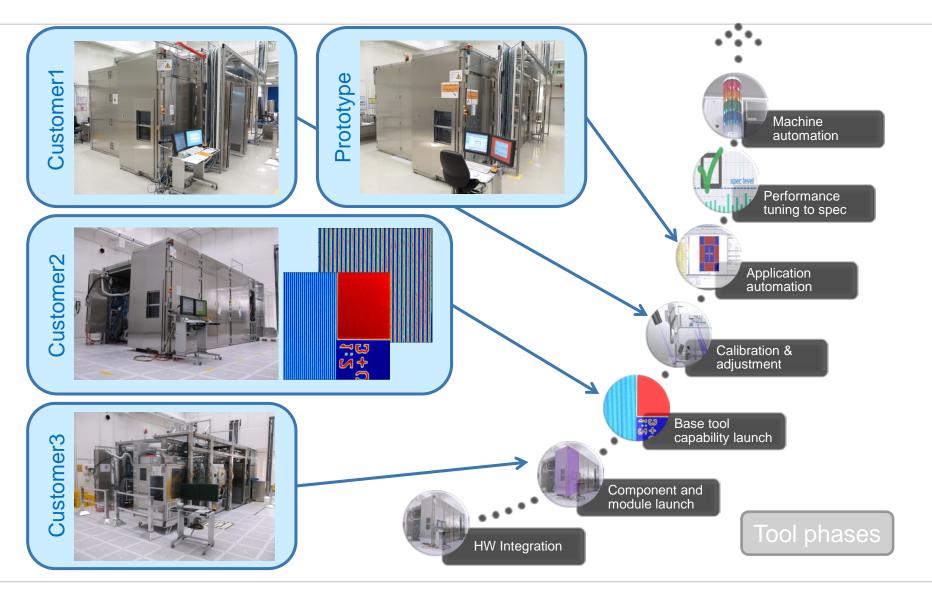
1	Current program phase and status
2	Achieved tool capabilities
3	First qualification results
4	Summary



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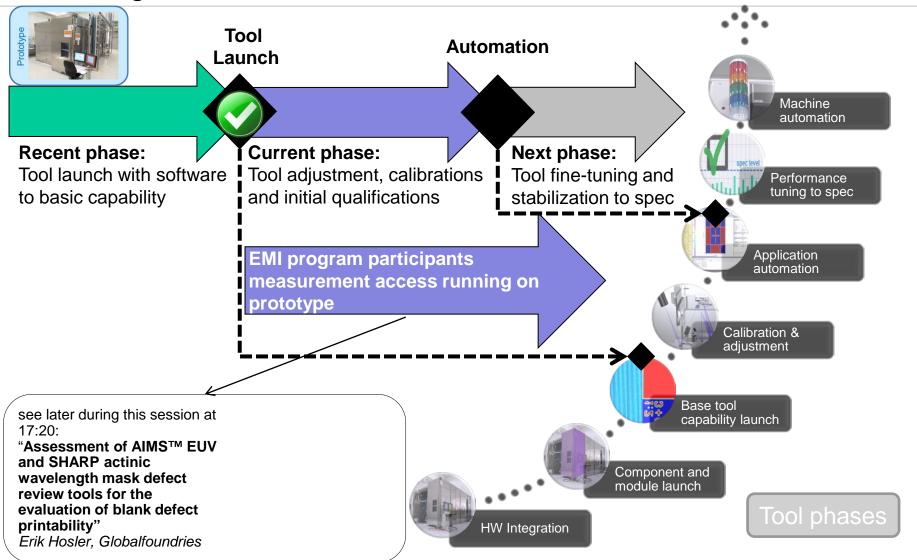
AIMS[™] EUV program status: 3rd tool has achieved First Light





AIMS[™] EUV program status: EMI program participants access to prototype running





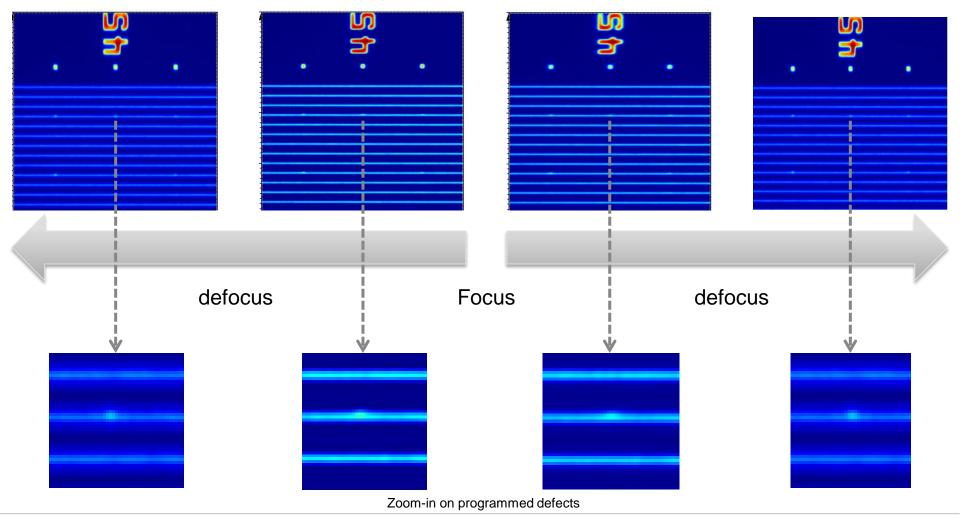


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EUV aerial image acquisition capability: Automated stack acquisition launched



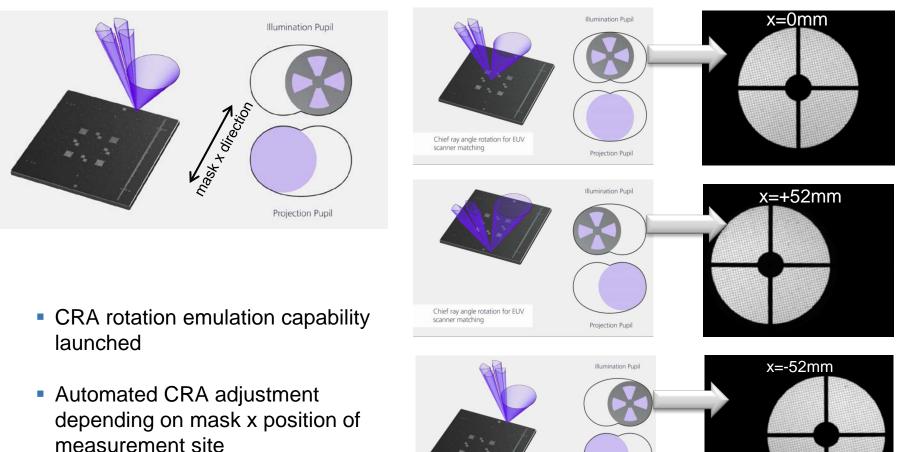
AIMS[™] EUV sample through focus stack acquired on prototype:



7

EUV aerial image acquisition capability: : Automated chief ray angle (CRA) rotation emulation launched





Prototype pupil images

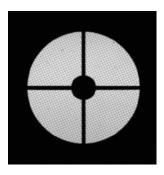
Carl Zeiss SMT, Sascha Perlitz, Product Management

Projection Pupil

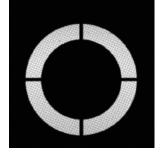
Handling capability: Mask and aperture handling capability established



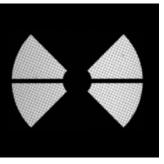
- Handling system launched
- Mask handling from load port to stage established for dual pod and RSP loading
- Inner handling system (in vacuum) also utilized to exchange illumination sigma apertures stored inside vacuum
- Pupil images of varying illumination settings used during prototype EMI access program



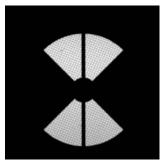
Conventional



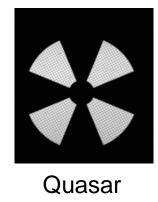
Annular



Dipole X



Dipole Y

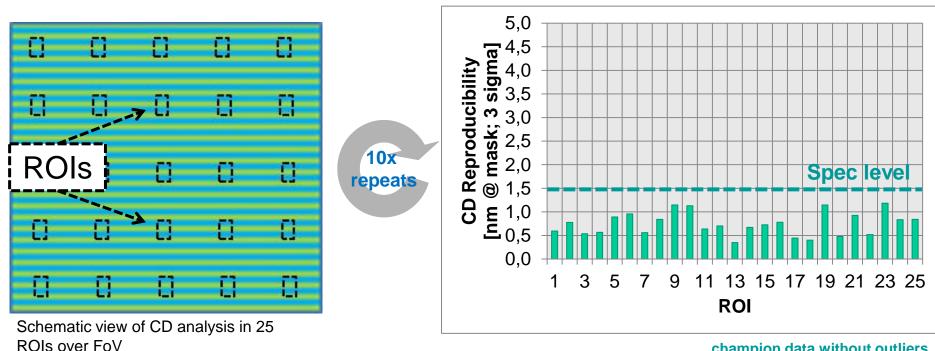




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First prototype qualification results: CD reproducibility champion data



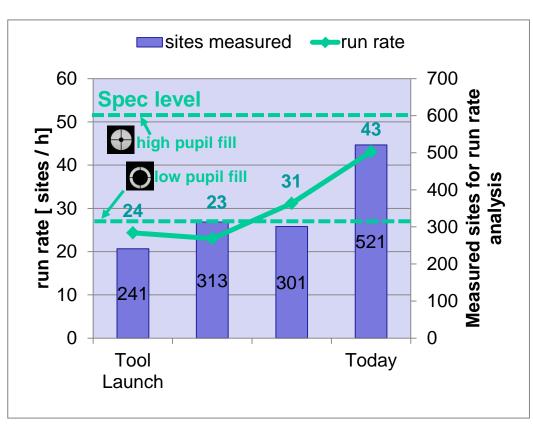


champion data without outliers

- CD evaluated on 25 regions of interest (ROI) over field of view (FoV)
- 10x Repeated dense L&S measurements
- Champion results indicate potential to reach in spec performance
- Outliers still need to be addressed
- Still high preparation effort on tool to produce such champion data

First prototype qualification results: Run-rate continuous improvements

- First run-rate results from EMI program participants access slots to prototype
- Continuous improvements on stack acquisition run-rate through software improvements seen after tool launch
- Current run-rate status is sufficient for optimizations for CD reproducibility
- Results based on mix of low and high pupil fill measurements

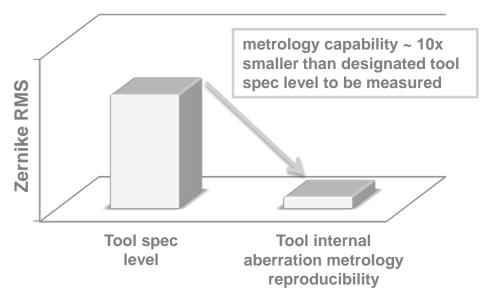




First prototype qualification results: 1st optics adjustment and tool internal EUV aberration metrology



- Prototype has entered phase of optics EUV fine alignment and adjustment
- In order to proceed in this fine alignment, tool internal aberration metrology was qualified
- metrology reproducibility capability tested to be ~10x smaller than designated spec level to be measured → metrology capability available
- First optics aberration qualification on prototype after initial alignment indicates safe in spec performance



First prototype qualification results:



First handling cycles particle test

Test cycle:

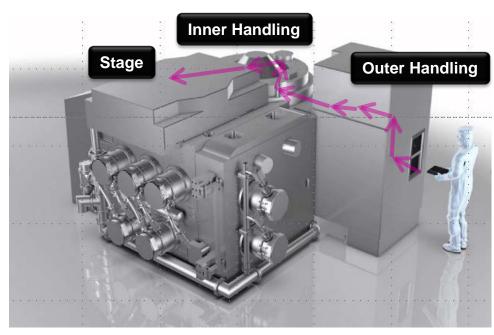
- Cycles from Outer Handling load port to stage and back
- Number of cycles: 142
- Not included in cycle: stage movements + measurements

Adder analysis:

 In-house blank inspection: particles on quality area >100nm size evaluated

Result

Good initial performance of:
0.19 adders / cycle





2 A	Achieved tool capabilities
3 Fi	First qualification results
4 S	Summary

Summary



Program status:

- Base image acquisition and handling capability launched
- EMI program participants access phase running on AIMS[™]EUV prototype
- Three tools now have 1st light

Performance status:

- Continuous improvements on stack acquisition run-rate through software improvements seen after tool launch
- First CD reproducibility champion data show potential for in-spec performance
- Tool internal aberration metrology capability verified
- Good initial blank adder performance for handling cycles from load port to stage



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We make it visible.